

REMARKS/ARGUMENTS

Claims 1, 3, 5-7, and 13-14 were rejected under 35 U.S.C. §103(a) as being unpatentable over Senda et al., U.S. Patent No. 5,990,417. Reconsideration of the rejection is respectfully requested.

In support of the rejection of independent claim 1, the Examiner alleges that, “Senda et al. ‘417 discloses a thickness of 0.1 microns (Col. 10, 11, Line 54-67, 1-2 respectively),” (Office Action, page 4, lines 5-6). Similarly, with regard to independent claims 13 and 14, the Examiner alleges that, “Senda et al. ‘417 discloses a thickness of 0.1 microns within the limitations of the claim (Col. 10, 11, Line 54-67, 1-2 respectively),” (Office Action, page 4, lines 14-15). Applicants respectfully submit that the previously quoted statements regarding Senda et al. do not adequately support the rejections of independent claim 1, 13, and 14.

Senda et al., in the portion thereof cited by the Examiner, discloses, “NiFe as the alloy magnetic substance, [and] SiO₂ as the non-magnetic insulating substance,” (column 10, lines 54-55; insertion in brackets in quotation; emphasis supplied). Senda et al. further states that, “[t]he thickness of the NiFe film was 1.5 μm ... and the SiO₂ film thickness was set to 0.1 μm,” (column 10, line 65, to column 11, line 1).

In contrast, independent claims 1, 13, and 14 claim an electromagnetic noise suppressor “wherein the electromagnetic noise suppressor includes a composite layer including a heterogeneous structure where a binding agent and a magnetic material are integrated at the nanometer scale, ... and the thickness of the composite layer is at least 0.005 μm and at most 0.3 μm,” (emphasis supplied).

Thus, from the portion of Senda et al. cited by the Examiner, it appears that only the thickness of SiO₂, the non-magnetic insulating substance, is 0.1 μm, whereas the thickness of the alloy magnetic substance NiFe is 1.5 μm. Independent claims 1, 13, and 14, however, require that the total thickness of the composite layer, including both a binding agent and a magnetic material, is at least 0.005 μm and at most 0.3 μm. The upper limit of the thickness of the composite layer, as provided in independent claims 1, 13, and 14, is, thus, 0.3 μm, which is less than the total thickness of both the NiFe layer and the SiO₂ layer disclosed in Senda et al. of 1.6 μm.

Since each of claims 3 and 5-7 is directly or indirectly dependent upon independent claim 1, each of claims 3 and 5-7 is allowable for at least the same reasons recited above with respect to the allowability of independent claim 1.

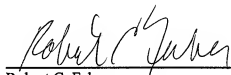
Any remarks or arguments presented in any previous Amendments, Responses, or Submissions filed by the Applicants in the above-captioned application are incorporated by reference in this paper, as if they were fully set forth in this paper, to the extent that such remarks or arguments are not inconsistent with the remarks or arguments presented above.

In view of the foregoing amendments and remarks, allowance of claims 1, 3, 5-7, 13, and 14 is respectfully requested.

Respectfully submitted,

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Robert C. Faber
Registration No.: 24,322
OSTROLENK, FABER, GERB & SOFFEN, LLP
1180 Avenue of the Americas
New York, New York 10036-8403
Telephone: (212) 382-0700